

Notice of References Cited	Application/Control No. 10/810,718	Applicant(s)/Patent Under Reexamination ANDRICACOS ET AL.	
	Examiner Edna Wong	Art Unit 1753	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2002/0112964	08-2002	Gandikota et al.	205/118
	B	US-6,113,771	09-2000	Landau et al.	205/123
	C	US-5,151,167	09-1992	Truong et al.	205/102
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Duboust et al., "Process Window For Electrochemical Deposition of High Aspect Ratio Structures", US Patent Application Serial No. 09/615,038, filed July 12, 2000.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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